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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
KAZUNORI IWAMOTO, ET AL.) : Examiner: P.S. Natividad
Application No.: 09/323,034) : Group Art Unit: 2877
Filed: June 1, 1999) :
For: SCANNING EXPOSURE METHOD) June 26, 2002
AND APPARATUS, AND DEVICE :
MANUFACTURING METHOD)
USING THE SAME) :

The Commissioner for Patents
Washington, D.C. 20231

AMENDMENT

RECEIVED
JUL - 8 2002
TC 2600 MAIL ROOM

Sir:

In response to the Office Action mailed March 26, 2002, the Examiner is respectfully requested to consider and enter the following amendments:

IN THE ABSTRACT:

Please rewrite the Abstract of the Disclosure as follows:

Q1
--A scan type exposure for transferring a pattern onto a substrate by scan exposure. The apparatus includes a stage for moving the substrate in a Y direction corresponding to a scan direction, and in an X direction intersecting the scan direction, an alignment scope for